## 论文

脉冲激光沉积氮化铝薄膜的电学性能研究

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摘要 采用脉冲激光沉积 (PLD) 技术在硅片上合成了AlN薄膜。X射线衍射 (XRD) 结果证实制备的AlN薄膜具有 (002) 择优取向的六方纤锌矿晶体结构,

给来证实制备的AIN薄膜具有(002)挥仇取问的八万纤锌矿 值件结构, 并且结晶质量随Si衬底温度的提高而改善。电流一电压(I-V)、电容一电压(C-V)、

极化曲线结果表明室温生长的AIN薄膜的击穿场强约2.5MV/cm,同时呈现明显的极化现象(类铁电),对应矫顽场强为150kV/cm,剩余极化为0.002 C/m2。晶态AIN存在较强的自发极化,薄膜中可动电荷密度高,据此提出了动态电荷模型,指出较大的AIN薄膜极化回线是由于可动电荷在电场中的再分布形成的,因而有别于铁电材料。

关键词 AIN薄膜 极化 电学性能

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## Electrical properties of AlN films prepared by pulsed laser deposition

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Abstract AlN films were synthesized on Si substrates by pulsed laser deposition (PLD). X-ray diffraction (XRD) spectra show that the films have a (002)-oriented hexagon wurstite crystalline structure and the crystallinity becomes better with higher substrate temperature. Current-voltage (I-V), capacitance-voltage (C-V) and polarization measurements demonstrate that the room-temperature grown sample has a breakdown field of 2.5MV/cm, and also a clear polarization hysteresis. Based on the intrinsic large spontaneous polarization in crystalline AlN and the large dynamic charge density in the samples, a dynamic charge model is proposed to interpret the observed polarization, which is due to redistribution of dynamic charges. Therefore it's different from ferroelectric materials.

Key words AlN films polarization electrical property

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